

English Translation of the Amendments to the Claims under PCT

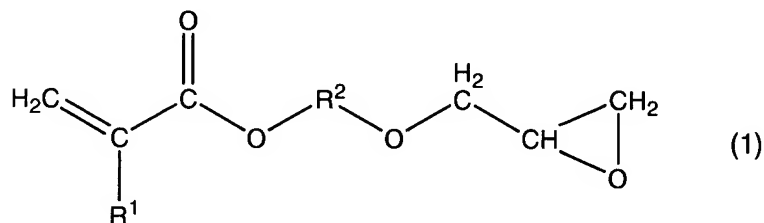
Article 19 (35 U.S.C.371(c)(2)).

## Claims

1. (Amended) A photosensitive resin composition  
characterized by comprising

a poly((meth)acrylic acid)-based water-soluble photo-sensitive resin (A) having an acid value of 170 mgKOH/g or more on a solid basis;

the resin (A) being formed of a ((meth)acrylic acid)-based polymer in which a compound represented by formula (1):



(wherein R<sup>1</sup> represents H or Me; and R<sup>2</sup> represents a linear or branched C2-C10 alkylene group) has been added to portions of the carboxylic groups,

a photopolymerization initiator (B); and

water (C).

2. A photosensitive resin composition according to claim 1, wherein the carboxyl groups of the ((meth)acrylic acid)-based polymer to which the compound represented by formula (1) has not been added are partially or entirely neutralized with an alkali.

3. (Amended) A method for forming a hydrogel

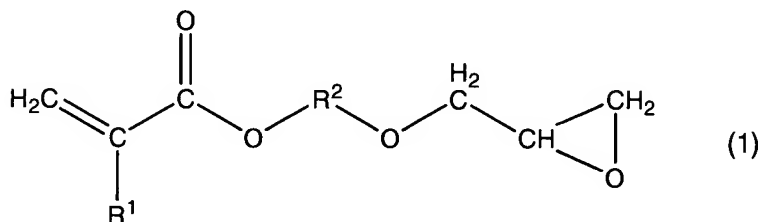
Art 19

characterized by comprising causing a photosensitive resin composition as recited in claim 1 or 2 to photopolymerize.

4. (Added) A hydrogel characterized by being produced by causing a photosensitive resin composition to photopolymerize, the photosensitive resin composition comprising

a poly((meth)acrylic acid)-based water-soluble photosensitive resin (A) having an acid value of 170 mgKOH/g or more on a solid basis;

the resin (A) being formed of a ((meth)acrylic acid)-based polymer in which a compound represented by formula (1):



(wherein  $\text{R}^1$  represents H or Me; and  $\text{R}^2$  represents a linear or branched C2-C10 alkylene group) has been added to portions of the carboxylic groups,

a photopolymerization initiator (B); and

water (C).

5. (Added) A hydrogel according to claim 4, wherein the carboxyl groups of the ((meth)acrylic acid)-based polymer to which the compound represented by formula (1) has not been added are partially or entirely neutralized with an alkali.